




## ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

<b>Title of Invention</b>	<b>METHOD FOR CONTROLLING A PROCESS FOR FABRICATING INTEGRATED DEVICES</b>																				
<p>Application Number: 10/805136 </p> <p>Confirmation Number: 8916</p> <p>First Named Applicant: Matthew Davis</p> <p>Attorney Docket Number: 8381/ETCH</p> <p>Search string: ( 6566025 ).pn.</p> <p><b>US Patent Documents</b></p> <p>Note: Applicant is not required to submit a paper copy of cited US Patent Documents</p> <table border="1"><thead><tr><th>init</th><th>Cite.No.</th><th>Patent No.</th><th>Date</th><th>Patentee</th><th>Kind</th><th>Class</th><th>Subclass</th></tr></thead><tbody><tr><td>MA</td><td>1</td><td>6566025</td><td>2003-05-20</td><td>McStravick et al.</td><td>B1</td><td></td><td></td></tr></tbody></table> <p><b>Signature</b></p> <table border="1"><thead><tr><th>Examiner Name</th><th>Date</th></tr></thead><tbody><tr><td>/Maki Angadi/</td><td>11/08/2006</td></tr></tbody></table>		init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass	MA	1	6566025	2003-05-20	McStravick et al.	B1			Examiner Name	Date	/Maki Angadi/	11/08/2006
init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass														
MA	1	6566025	2003-05-20	McStravick et al.	B1																
Examiner Name	Date																				
/Maki Angadi/	11/08/2006																				

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)					Docket No. 8381/ETCH/SILICON/JB1		Serial No. 10/805,136	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>					Applicant Davis, et al.		Confirmation No.: 8916	
(Use several sheets if necessary)					Filing Date March 19, 2004		Group	
Examiner								
<b>U.S. Patent Documents</b>								
*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate	
	A1	4,767,496	08/30/1988	Hieber	156	627		
	A2	5,798,529	08/25/1998	Wagner	250	492.2		
	A3	5,926,690	07/20/1999	Toprac et al.	438	17		
	A4	5,948,203	09/07/1999	Wang	156	345		
	A5	6,004,706	12/21/1999	Ausschnitt et al.	430	30		
	A6	6,027,842	02/22/2000	Ausschnitt et al.	430	30		
	A7	6,161,054	12/12/2000	Rosenthal et al.	700	121		
	A8	6,245,581	06/12/2001	Bonser et al.	438	8		
	A9	6,424,417	07/23/2002	Cohen et al.	356	388		
	A10	6,486,492	11/26/2002	Su	257	48		
✓	MA	A11	2002/0171828	Cohen et al.	356	328	07/01/2002	
<b>Foreign Patent Documents</b>								
*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1						<input type="checkbox"/>	<input type="checkbox"/>
	B2						<input type="checkbox"/>	<input type="checkbox"/>
<b>OTHER ART</b>								
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.						
MA	C1	Lee, et al., "Analysis of Reflectometry and Ellipsometry Data from Patterned Structures," Characterization and Metrology for UCSI Technology: 1998 International Conference, Seiler, et al., eds., pg 331-335						
MA	C2	Raymond, "Angle-resolved scatterometry for semiconductor manufacture," Microlithography World, Winter 2000.						
MA	C3	Toprac, A., "AMD's Advanced Process Control of Ply-Gate Critical Dimension," Proc. SPIE Vol 3882, pg 62-65, Sept, 1999.						
MA	C4	Yang, et al., "Line-profile and Critical Dimension Measurements Using a Normal Incidence Optical Metrology System," Proceedings of SPIE Vol. 4689, March 2002,						
Examiner /Maki Angadi/					Date Considered 11/08/2006			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								